

PROCEEDINGS OF SPIE

Instrumentation, Metrology, and Standards for Nanomanufacturing IV

Michael T. Postek
John A. Allgair
Editors

2–4 August 2010
San Diego, California, United States

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Published by
SPIE

Volume 7767

Proceedings of SPIE, 0277-786X, v. 7767

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Author(s), "Title of Paper," in *Instrumentation, Metrology, and Standards for Nanomanufacturing IV*, edited by Michael T. Postek, John A. Allgair, Proceedings of SPIE Vol. 7767 (SPIE, Bellingham, WA, 2010) Article CID Number.

ISSN 0277-786X
ISBN 9780819482631

Published by

SPIE

P.O. Box 10, Bellingham, Washington 98227-0010 USA
Telephone +1 360 676 3290 (Pacific Time) · Fax +1 360 647 1445
SPIE.org

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